

(12) INTERNATIONAL APPLICATION PUBLISHED UNDER THE PATENT COOPERATION TREATY (PCT)

(19) World Intellectual Property Organization International Bureau



(43) International Publication Date  
21 October 2004 (21.10.2004)

PCT

(10) International Publication Number  
**WO 2004/090017 A1**

(51) International Patent Classification<sup>7</sup>: C08G 73/10,  
C07D 251/00, G02F 1/1337

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(21) International Application Number:  
PCT/KR2004/000102

(22) International Filing Date: 20 January 2004 (20.01.2004)

(25) Filing Language: Korean

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110-618 (KR).

(26) Publication Language: English

(81) Designated States (unless otherwise indicated, for every  
kind of national protection available): AE, AG, AL, AM,  
AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA, CH, CN,  
CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI,  
GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE,  
KG, KP, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG,  
MK, MN, MW, MX, MZ, NA, NI, NO, NZ, OM, PG, PH,  
PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SY, TJ, TM, TN,  
TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW.

(30) Priority Data:  
10-2003-0022261 9 April 2003 (09.04.2003) KR

(84) Designated States (unless otherwise indicated, for every  
kind of regional protection available): ARIPO (BW, GH,  
GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZM, ZW),  
Eurasian (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM), European  
(AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR,

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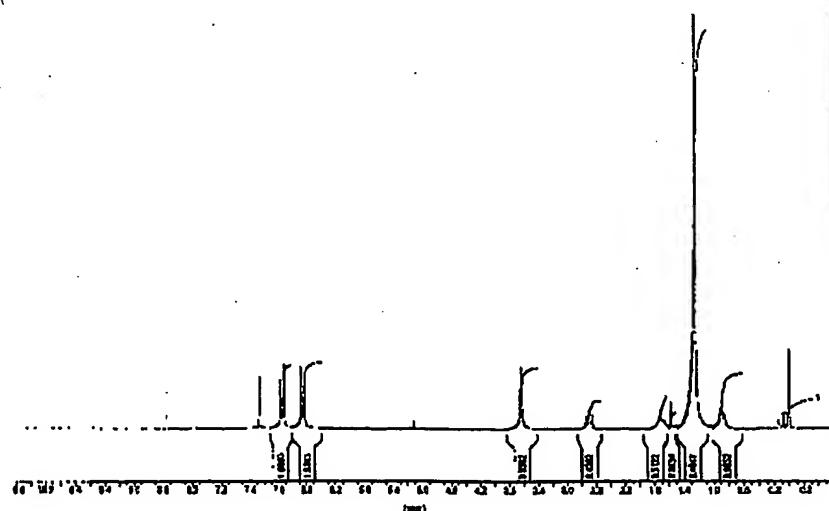
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[Continued on next page]

(54) Title: DIAMINE COMPOUND CONTAINING TRIAZINE GROUP, POLYAMIC ACID SYNTHESIZED FROM THE DIAMINE COMPOUND AND LC ALIGNMENT FILM PREPARED FROM THE POLYAMIC ACID

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(57) Abstract: Diamine compound containing specific triazine group, polyamic acid obtained by reacting the diamine compound and tetracarboxylic dianhydride, and liquid crystal alignment film obtained by coating and imidizing the polyamic acid. The liquid crystal alignment film has good heat-resistance, high transparency in visible light region and improved voltage holding ratio. Also, pretilt angle is easily controlled over broad range.